

# All-Silicon Modules

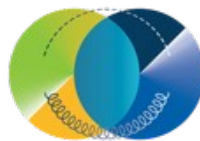
VTX Workshop  
April 2026 at Desy

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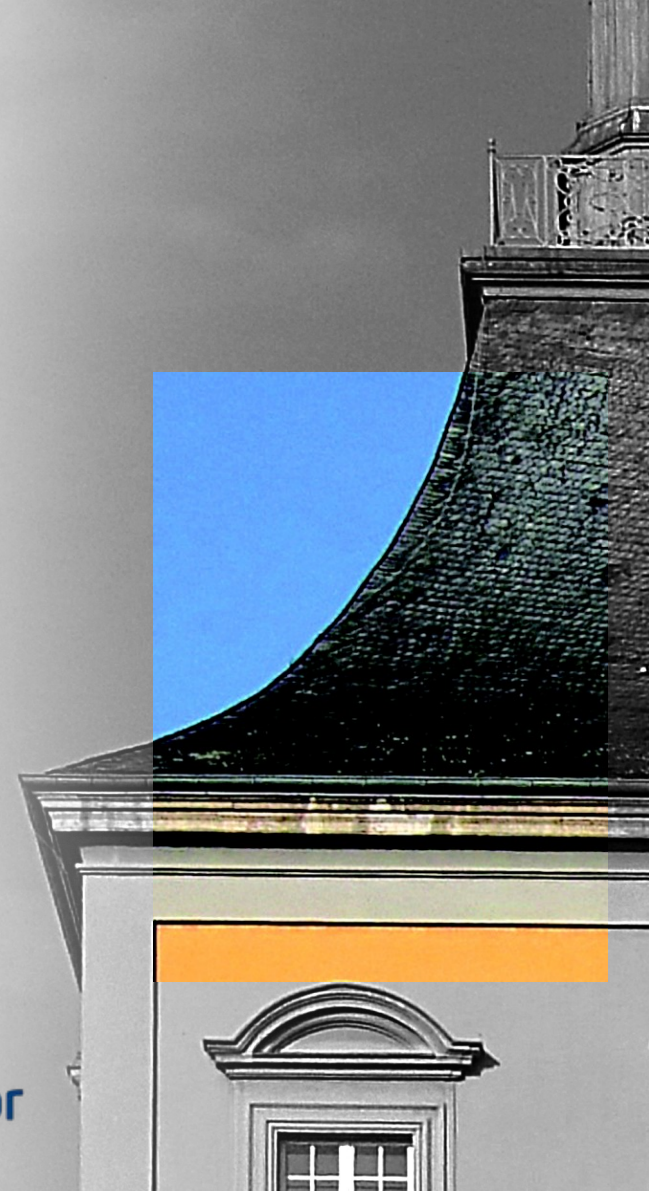
Physikalisches Institut der Universität Bonn



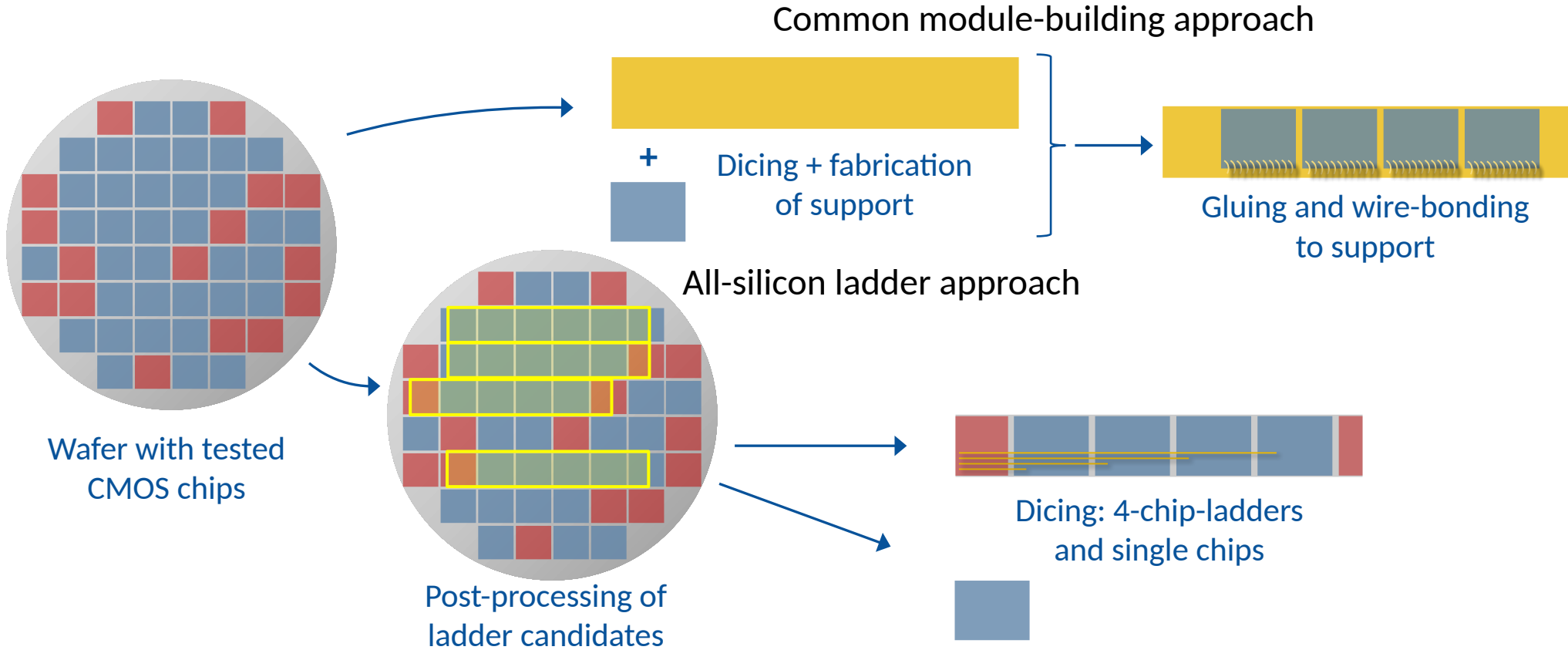
Bundesministerium  
für Forschung, Technologie  
und Raumfahrt



color meets flavor



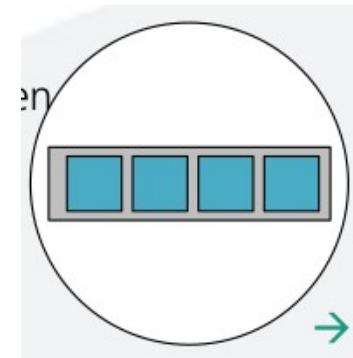
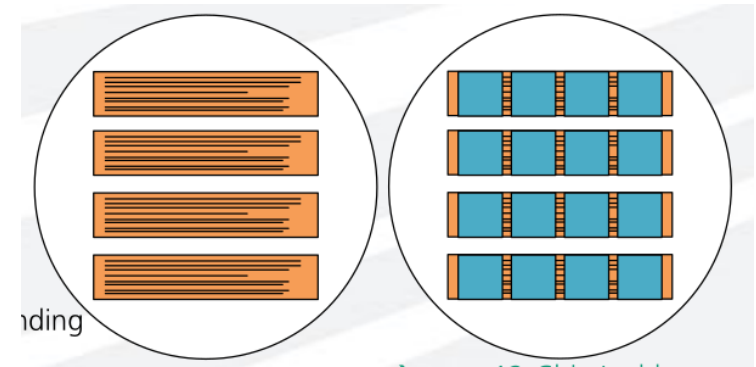
# All-Silicon Modules concept



# IZM manufacturing options

## Two Options how to produce All-Silicon Modules

- RDL first approach:
  - Build RDL layers on carrier wafer
  - Dice all chips
  - Bond chips on carrier and glue everything together
  - Thinning and carrier removal
- Ladder first approach:
  - Dice ladders (and remaining chips) from wafer
  - Process ladders in a “chip”-process on carrier wafer with RDL layers
  - Thinning and carrier removal
- Wafer level processing not feasible



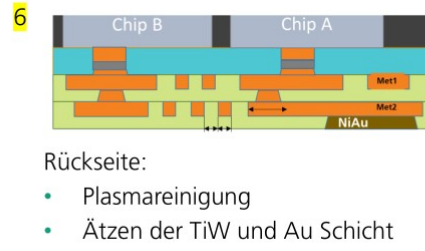
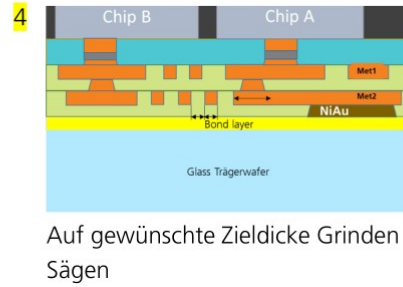
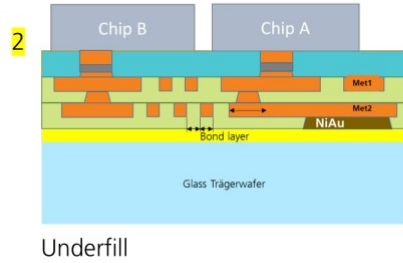
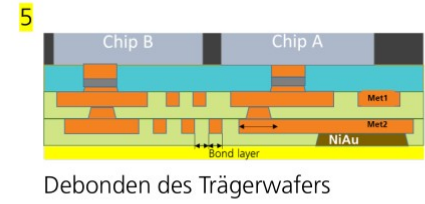
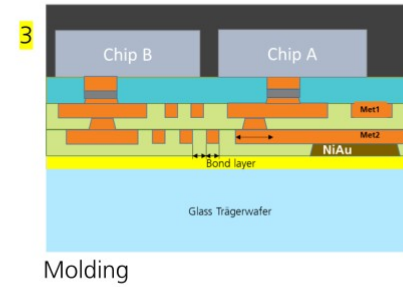
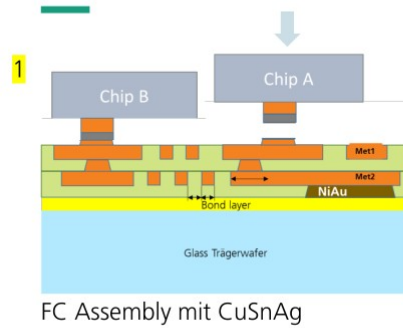
# IZM manufacturing options: RDL first

## RDL First Ansatz

Open question:

- What material for mold
- Mechanical properties
- Thermal properties
- Material budget
- RDL thickness

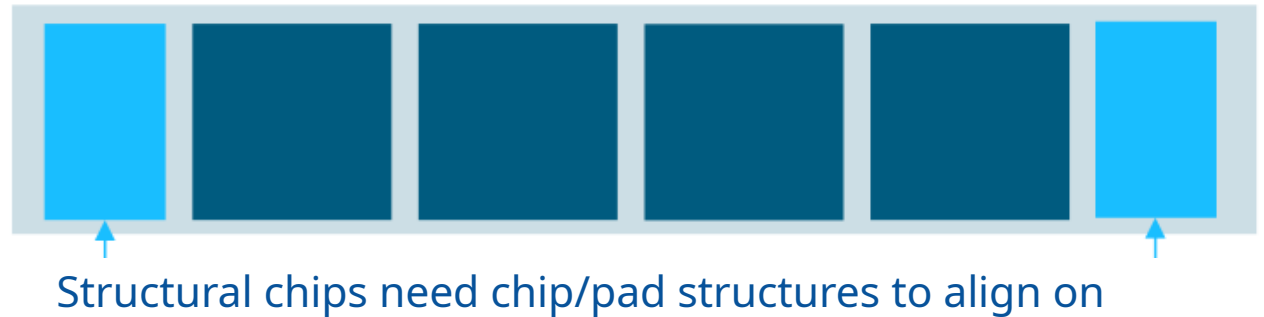
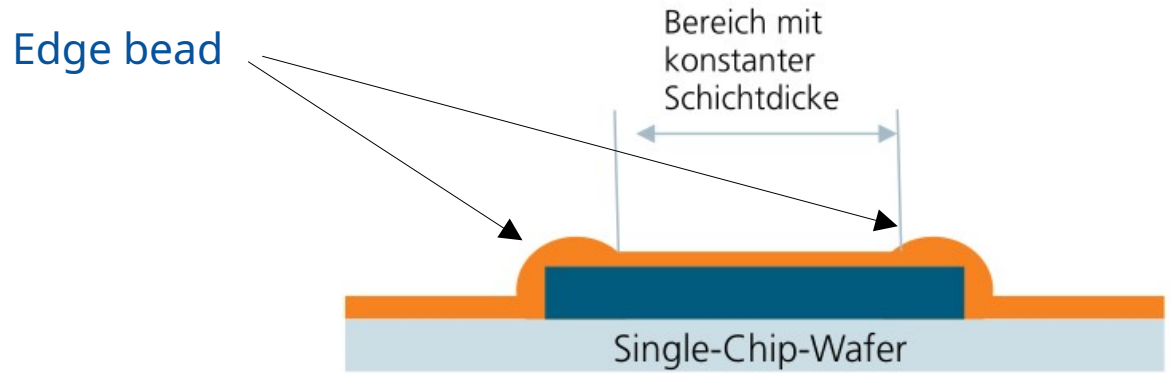
Currently not preferred  
 but possible backup if  
 ladder first approach not  
 working



## IZM manufacturing options: Ladder first

For ladder first to work:

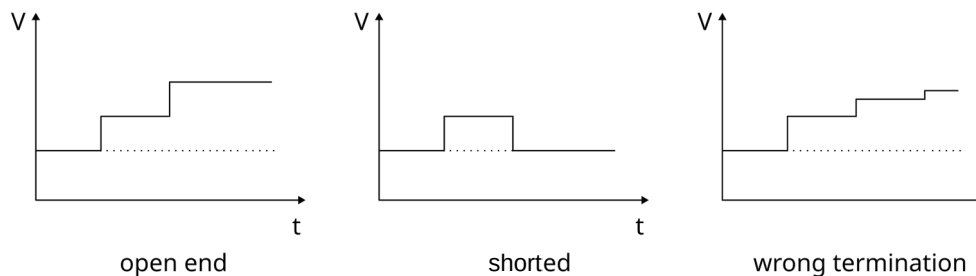
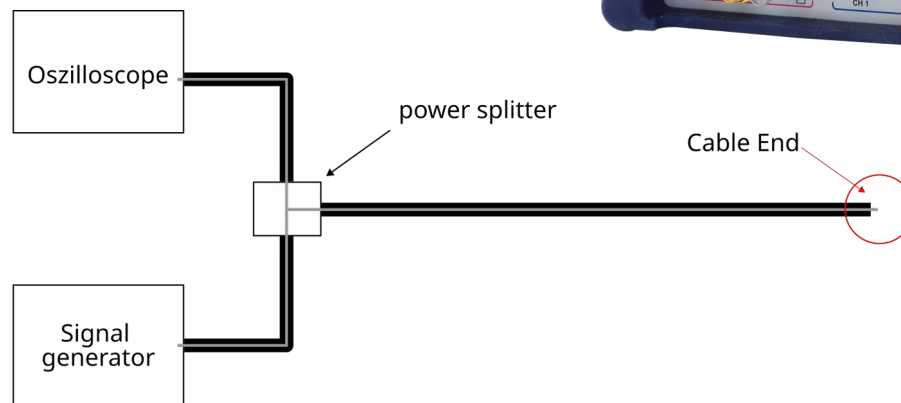
- Need chip structure to each side of the ladder for alignment
- Investigation ongoing regarding layer thickness on edges and suppression of edge bead
- Cost unclear
  - Process development
  - Obelix prototype
  - Obelix production



# TDR - Time domain reflectometry

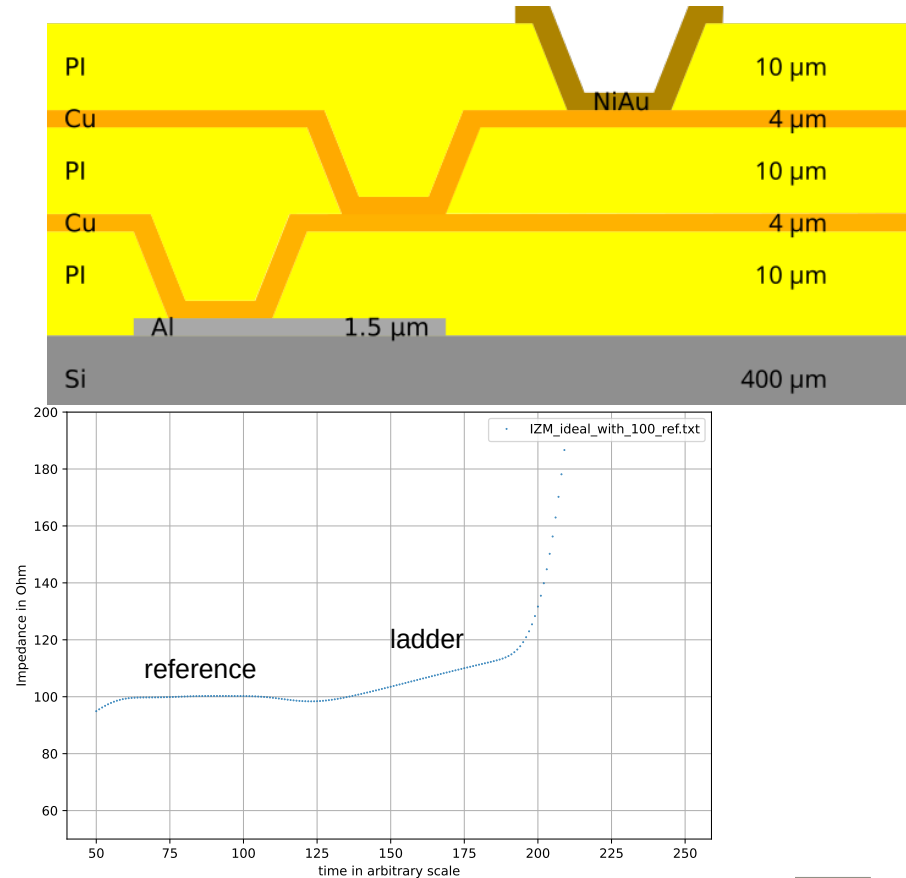
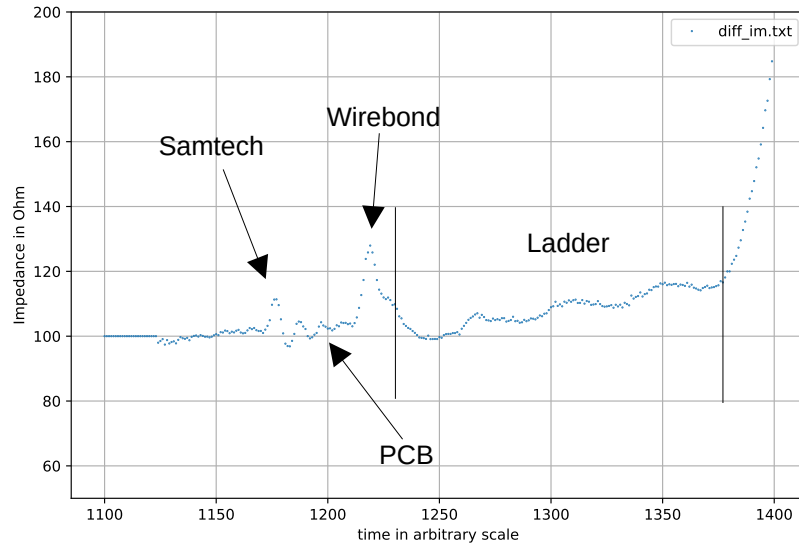


- Send electrical pulse and measure reflection
- Important is sharp edge at the beginning
- Method used to measure
  - Cable length
  - Defects
  - Shorts
  - Changes of impedance
  - Etc.

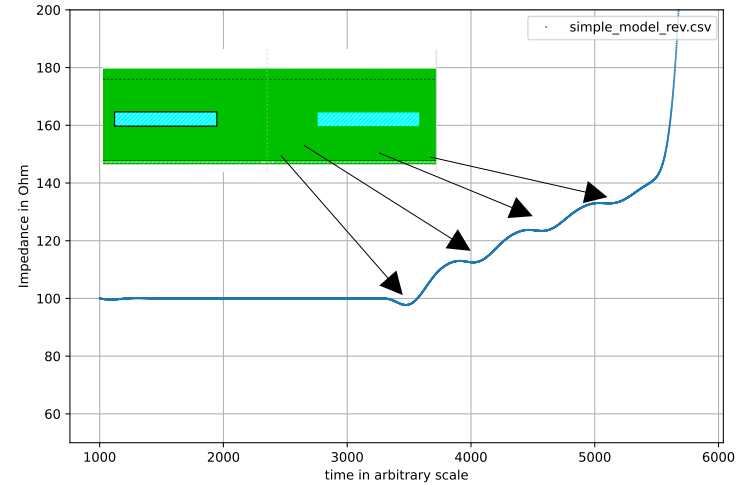
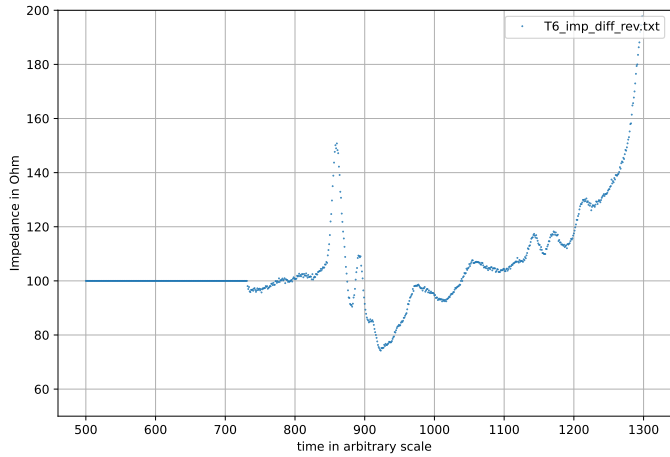
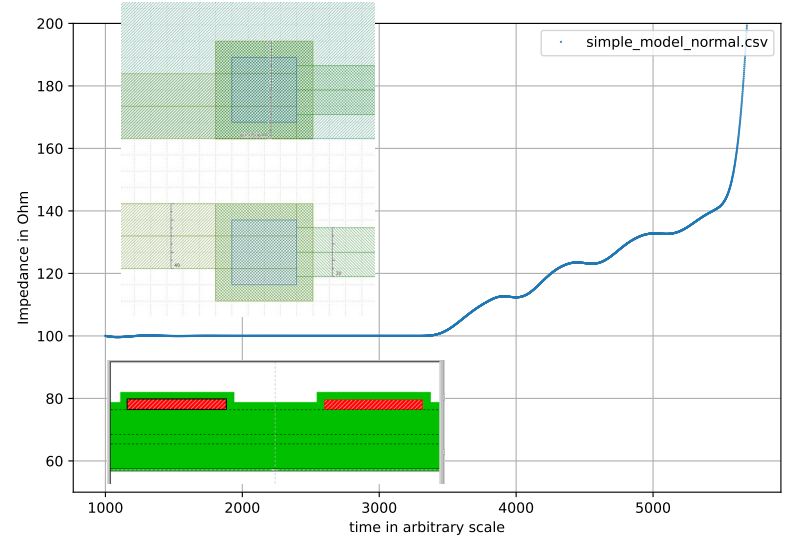
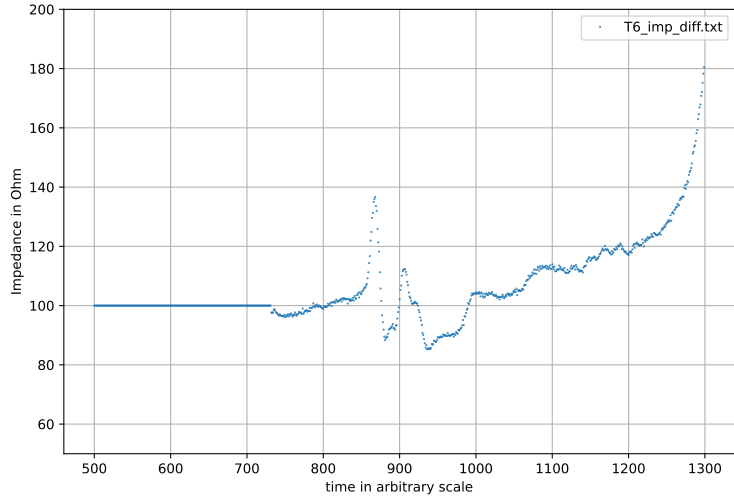


# Layer Stack-up IZM ordered

- width/gap: 40/40
- Simulation:  $Z_0 = 99.4\Omega$

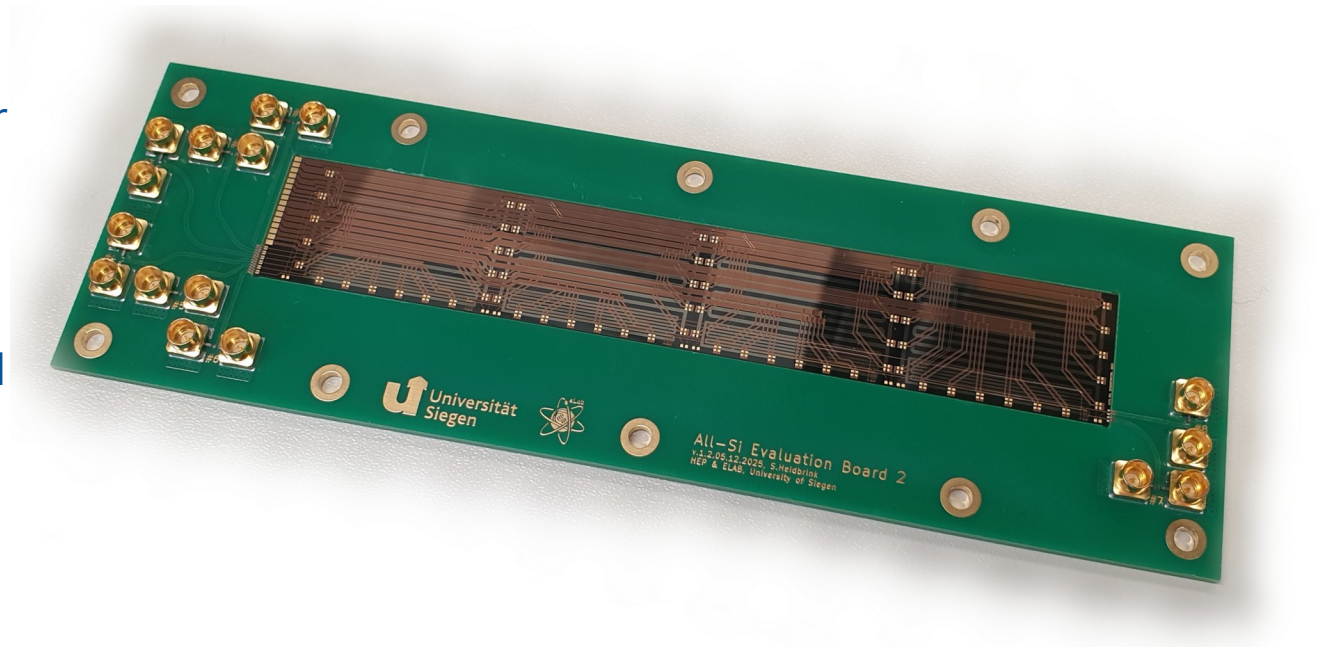


# Layer Stack-up IZM ordered



# Eye diagram measurements on IZM modules

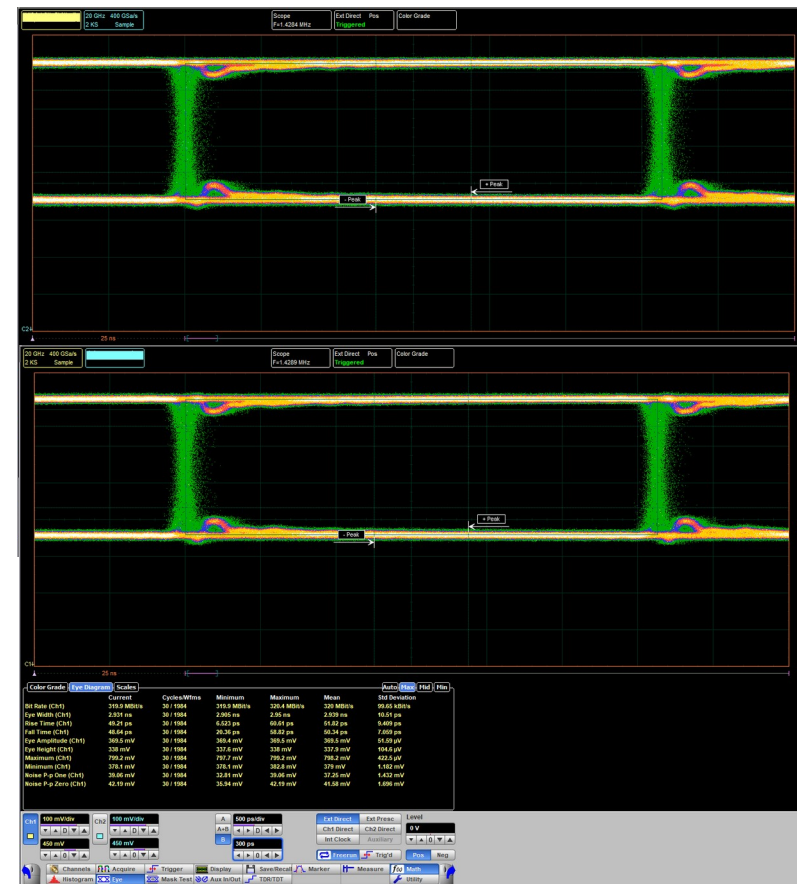
- PCB from Siegen used for measurements of TDR and Eyediagram
- Created 8b/10b encoding patter with signal generator
- Measured with oscilloscope
- S-parameter measurements will follow



# Eye diagram measurements on IZM modules

- Reference measurement with 20cm long cables
- Measurement on CMD/CLK traces T5 and T6
- Measured each channel individually and differentially

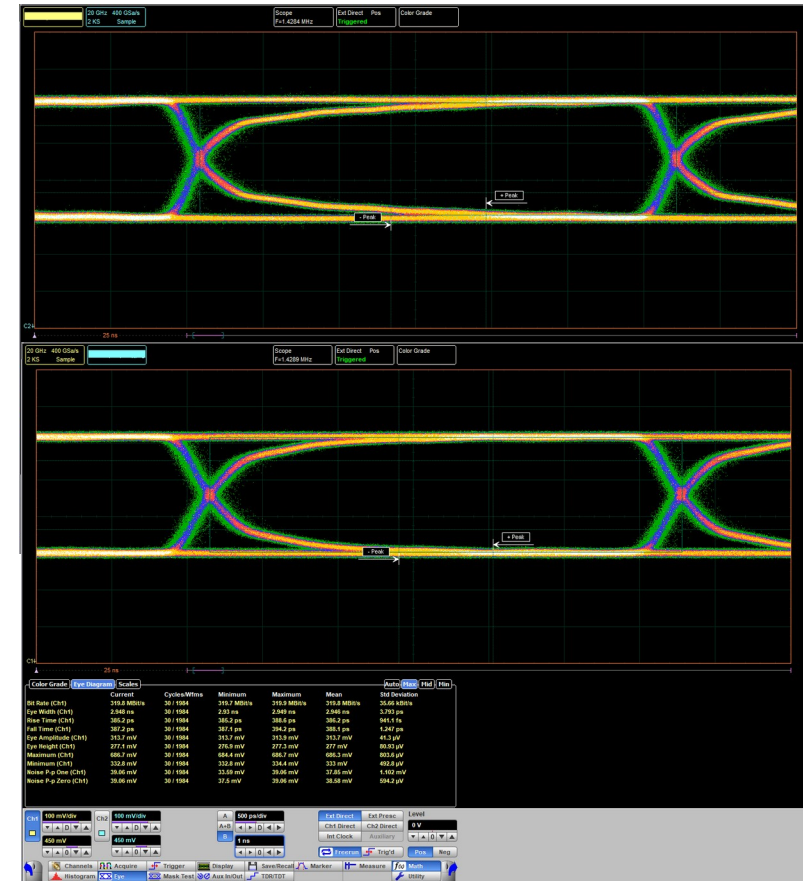
	Current	Cycles/Wfms	Minimum	Maximum	Mean	Std Deviation
Bit Rate (Ch1)	319.9 MBit/s	30 / 1984	319.9 MBit/s	320.4 MBit/s	320 MBit/s	99.65 kBit/s
Eye Width (Ch1)	2.931 ns	30 / 1984	2.905 ns	2.939 ns	2.939 ns	10.51 ps
Rise Time (Ch1)	49.21 ps	30 / 1984	6.523 ps	60.61 ps	51.82 ps	9.409 ps
Fall Time (Ch1)	48.64 ps	30 / 1984	20.36 ps	58.82 ps	50.34 ps	7.059 ps
Eye Amplitude (Ch1)	369.5 mV	30 / 1984	369.4 mV	369.5 mV	369.5 mV	51.59 $\mu$ V
Eye Height (Ch1)	338 mV	30 / 1984	337.6 mV	338 mV	337.9 mV	104.6 $\mu$ V
Maximum (Ch1)	799.2 mV	30 / 1984	797.7 mV	799.2 mV	798.2 mV	422.5 $\mu$ V
Minimum (Ch1)	378.1 mV	30 / 1984	378.1 mV	382.8 mV	379 mV	1.182 mV
Noise P-p One (Ch1)	39.06 mV	30 / 1984	32.81 mV	39.06 mV	37.25 mV	1.432 mV
Noise P-p Zero (Ch1)	42.19 mV	30 / 1984	35.94 mV	42.19 mV	41.58 mV	1.696 mV



# Eye diagram measurements on IZM modules T5

- 400mV DC offset + 400mV PP per channel
- Eyes wide open
- Rise time <400ps
- Bit rate 320MHz
- Differential eye amplitude 620mV (>300mV per channel)

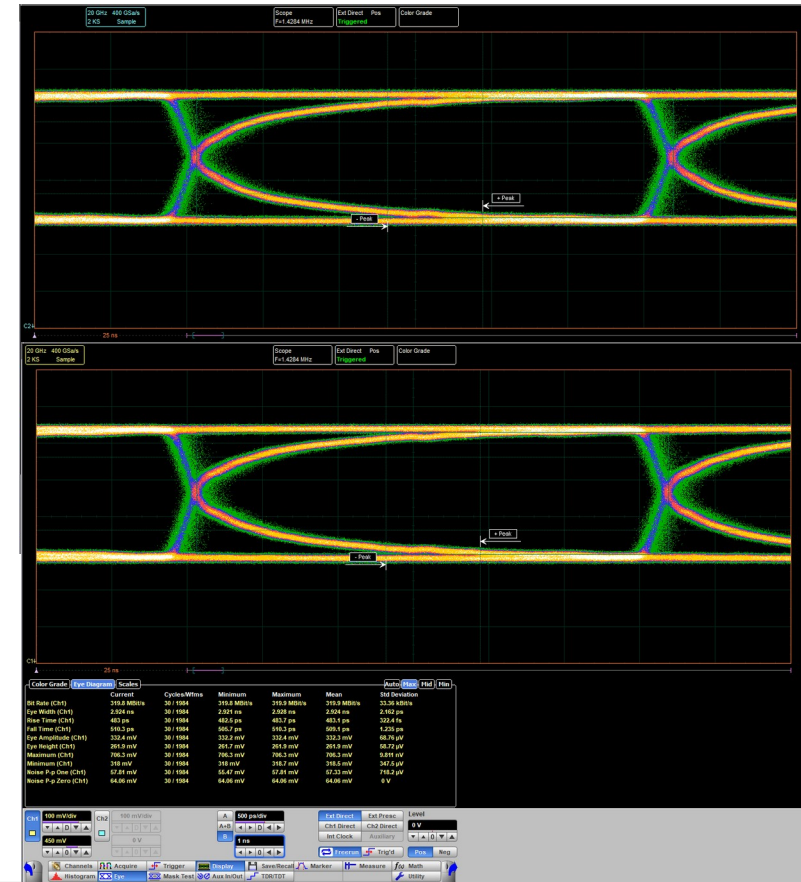
	Current	Cycles/Wfms	Minimum	Maximum	Mean	Std Deviation
Bit Rate (F1)	319.8 MBit/s	32 / 2112	319.5 MBit/s	319.8 MBit/s	319.8 MBit/s	72.05 kBit/s
Eye Width (F1)	2.948 ns	32 / 2112	2.941 ns	2.959 ns	2.947 ns	4.178 ps
Rise Time (F1)	377.6 ps	32 / 2112	365.9 ps	378 ps	376.1 ps	2.275 ps
Fall Time (F1)	376.4 ps	32 / 2112	372.2 ps	378.2 ps	375.5 ps	1.252 ps
Eye Amplitude (F1)	617.7 mV	32 / 2112	617.3 mV	617.7 mV	617.5 mV	124.1 $\mu$ V
Eye Height (F1)	525.5 mV	32 / 2112	524.9 mV	525.5 mV	525.3 mV	186 $\mu$ V
Maximum (F1)	353.9 mV	32 / 2112	353.9 mV	353.9 mV	353.9 mV	9.43 nV
Minimum (F1)	-346.1 mV	32 / 2112	-346.1 mV	-343 mV	-345.9 mV	690.1 $\mu$ V
Noise P-p One (F1)	84.37 mV	32 / 2112	75.78 mV	84.37 mV	82.81 mV	2.278 mV
Noise P-p Zero (F1)	85.94 mV	32 / 2112	78.91 mV	85.94 mV	84.99 mV	1.951 mV



# Eye diagram measurements on IZM modules T6

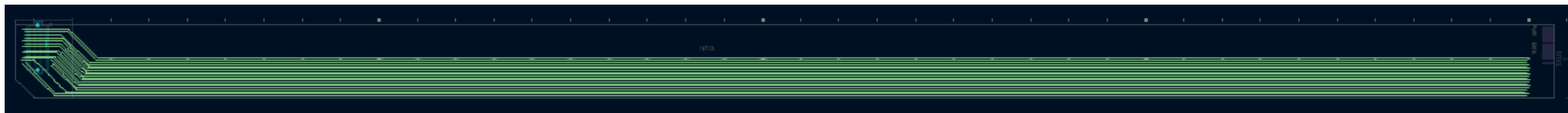
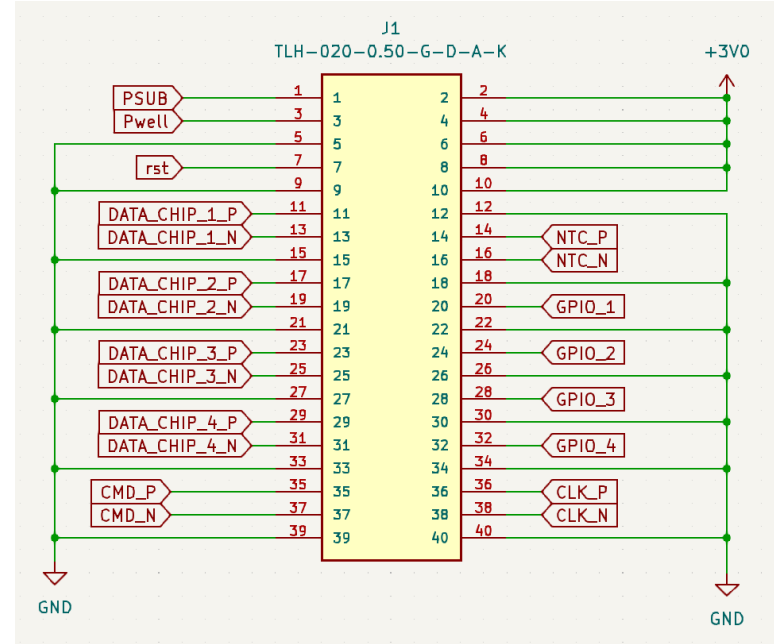
- 400mV DC offset + 400mV PP per channel
- Eyes wide open
- Rise time <400ps
- Bit rate 320MHz
- Differential eye amplitude 660mV (>300mV per channel)

	Current	Cycles/Wfms	Minimum	Maximum	Mean	Std Deviation
Bit Rate (F1)	320 MBit/s	31 / 2048	320 MBit/s	320.1 MBit/s	320 MBit/s	9.561 kBit/s
Eye Width (F1)	2.947 ns	31 / 2048	2.947 ns	2.949 ns	2.949 ns	1 ps
Rise Time (F1)	479.2 ps	31 / 2048	479.1 ps	480 ps	479.4 ps	256.3 fs
Fall Time (F1)	491.2 ps	31 / 2048	490.3 ps	491.3 ps	490.7 ps	366.3 fs
Eye Amplitude (F1)	657.4 mV	31 / 2048	657.2 mV	657.4 mV	657.3 mV	48.2 $\mu$ V
Eye Height (F1)	524.4 mV	31 / 2048	524.2 mV	524.3 mV	524.3 mV	50.86 $\mu$ V
Maximum (F1)	380.5 mV	31 / 2048	379.7 mV	380.5 mV	379.9 mV	343.7 $\mu$ V
Minimum (F1)	-380.5 mV	31 / 2048	-380.5 mV	-380.5 mV	-380.5 mV	6.58 nV
Noise P-p One (F1)	110.9 mV	31 / 2048	110.9 mV	110.9 mV	110.9 mV	1.104 nV
Noise P-p Zero (F1)	118.7 mV	31 / 2048	114.8 mV	118.7 mV	117 mV	804.5 $\mu$ V



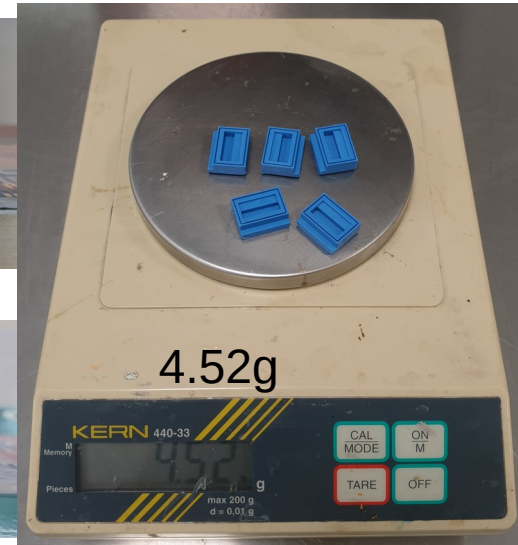
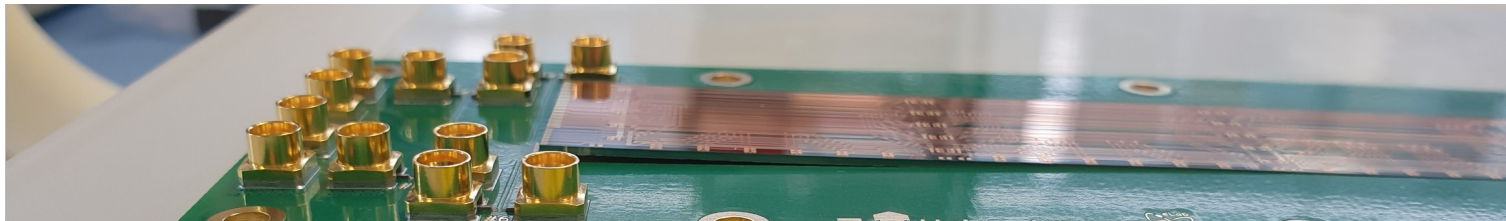
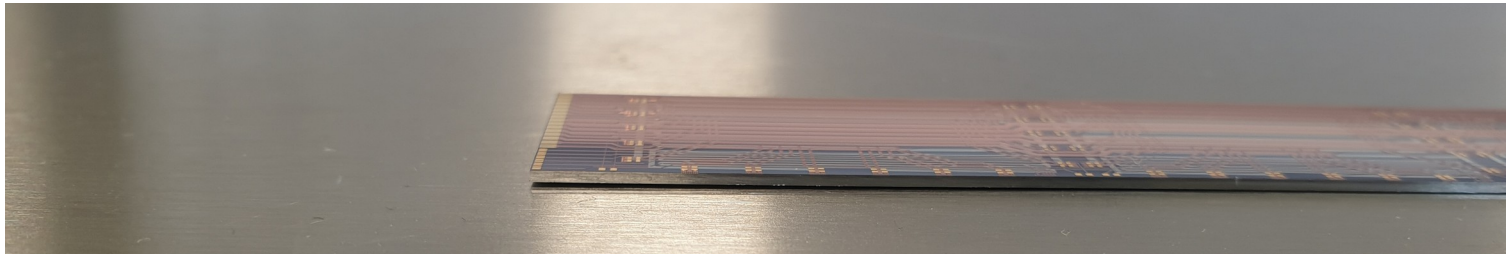
# Flex Cable to iVTX

- 3 layer Flexcable with signals in middle, power on top and bottom layer
- Connection to IpGBT PCB via TLH-020-0.50-G-D-A  
Connection to iVTX via wirebond pads
- 4x Chip data, CMD, CLK, RST, 4x ADC\_Cal, on ladder NTC, PWR, GND, Sub, Well
- 40cm length (similar to PXD)  
1.9cm width (to fit iVTX ladder)



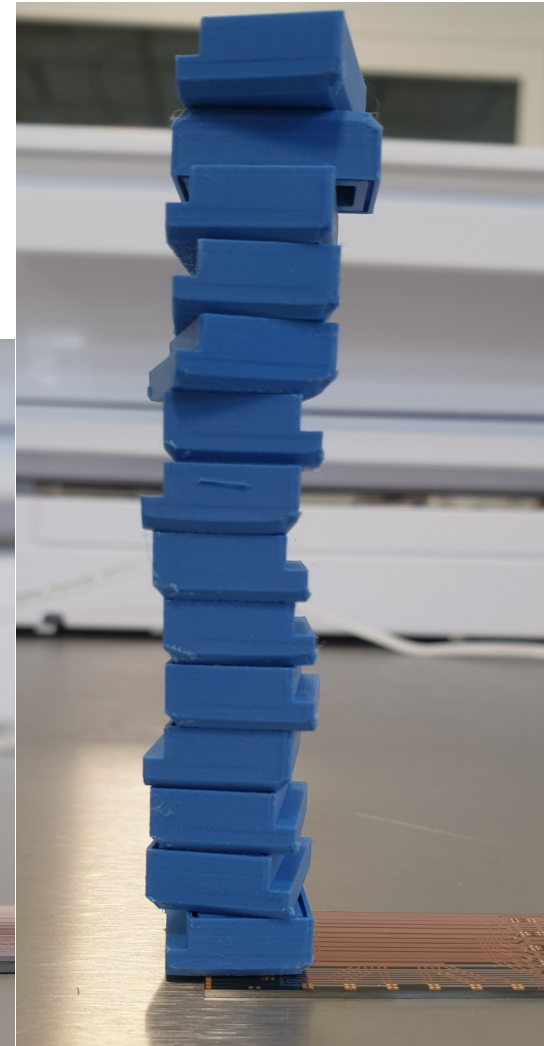
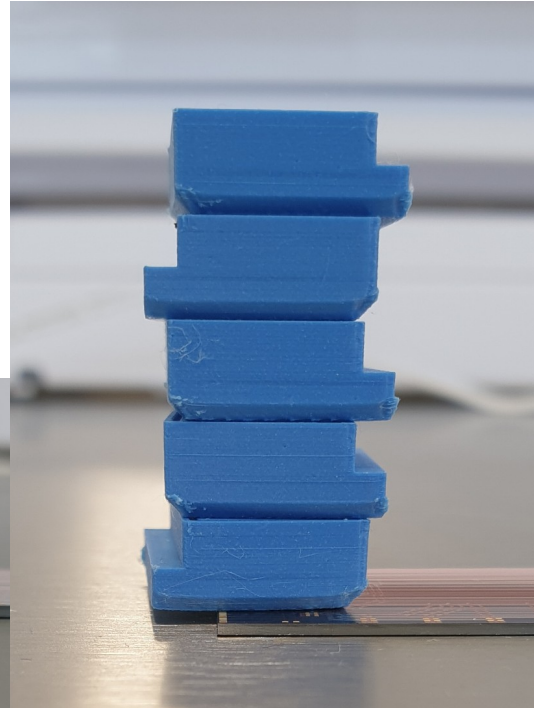
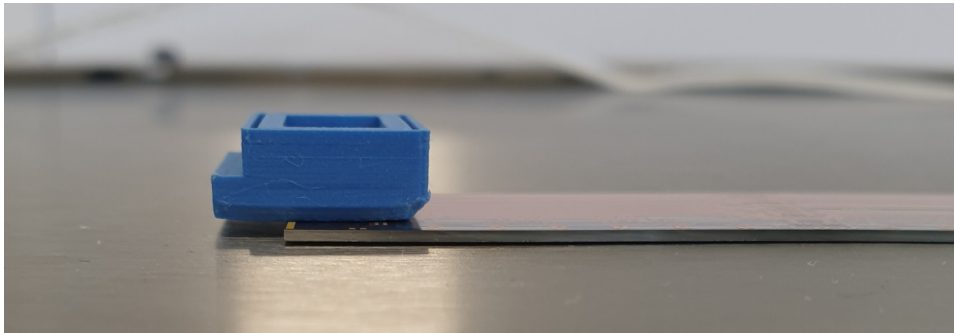
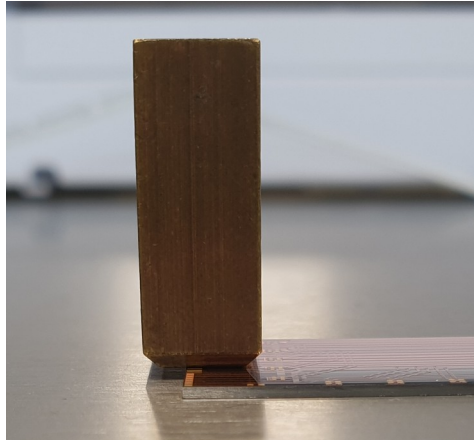
## Bending issues

- Quick approximation of bending on IZM modules (725um thickness, 12.5cm length)
- 40g weight on one side, increase weight on other side until bending disappears



## Bending issues

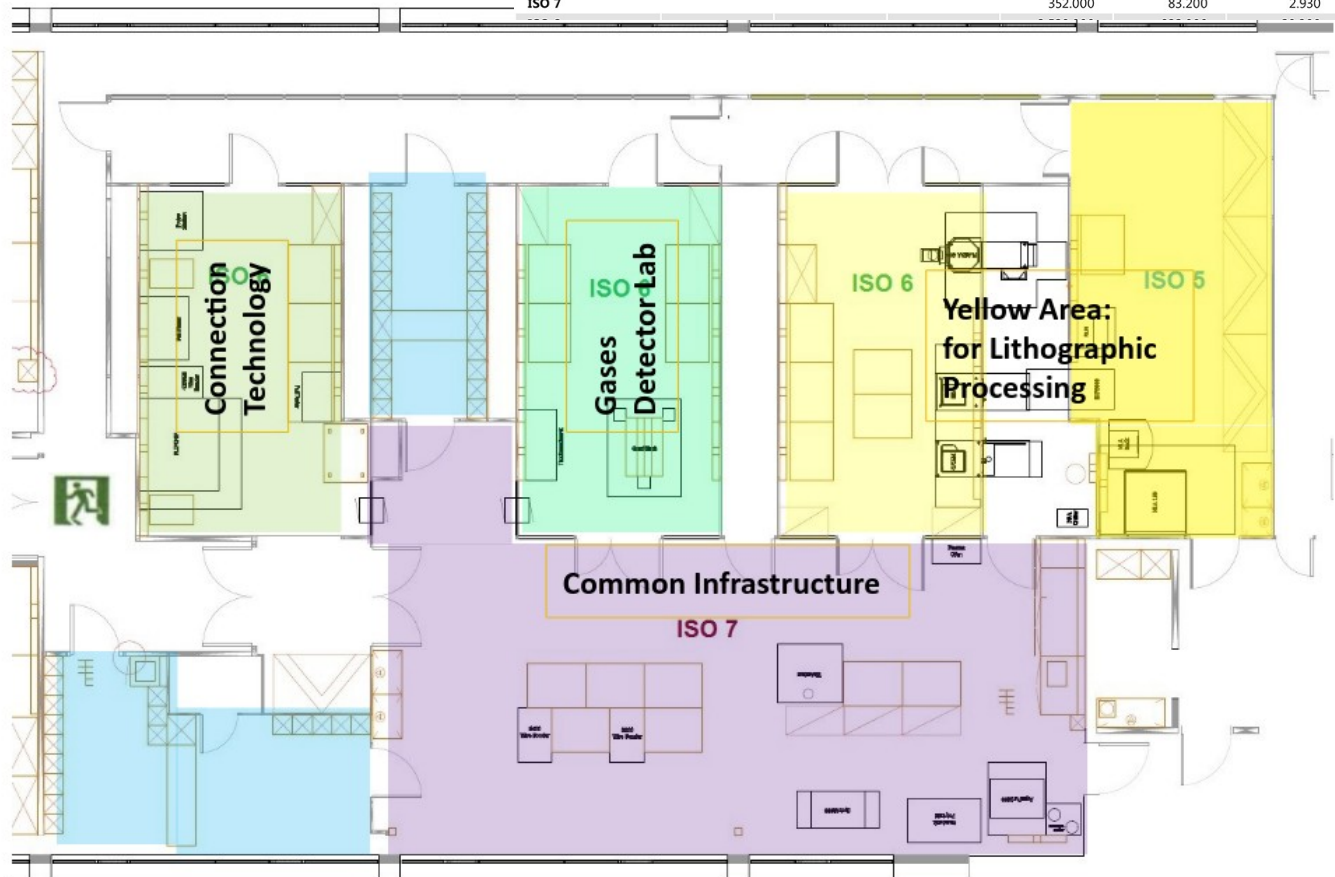
- Tried with
  - 1 part (0.5g)
  - 5 parts (4.5g)
  - 15 parts (13.5g)
  - 20.5g weight



# FTD Cleanroom

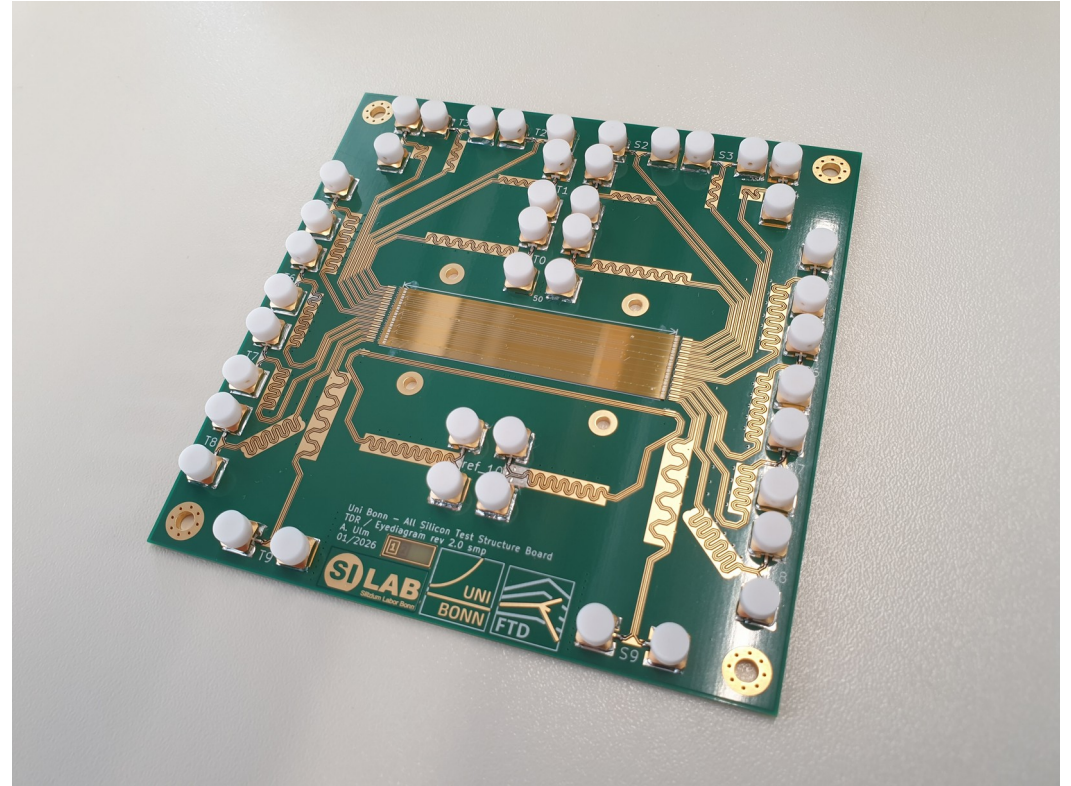
DIN EN ISO 14644-1 Klasse	Höchstwert der zulässigen Konzentration (Partikel je m <sup>3</sup> )					
	≥ 0,1 µm	≥ 0,2 µm	≥ 0,3 µm	≥ 0,5 µm	≥ 1,0 µm	≥ 5,0 µm
ISO 1	10					
ISO 2	100	24	10			
ISO 3	1.000	237	102	35		
ISO 4	10.000	2.370	1.020	352	83	
ISO 5	100.000	23.700	10.200	3.520	832	
ISO 6	1.000.000	237.000	102.000	35.200	8.320	293
ISO 7				352.000	83.200	2.930

- ca. 350m<sup>2</sup> Cleanroom area
- Classes ISO 7 to ISO 5
- ISO 7 currently mostly occupied by ATLAS production
- ISO 6 area assigned to Interconnection Technologies and Wafer probing as well as Gaseous Detectors
- Yellow light area (ISO 6 and 5) used for photolithography processing



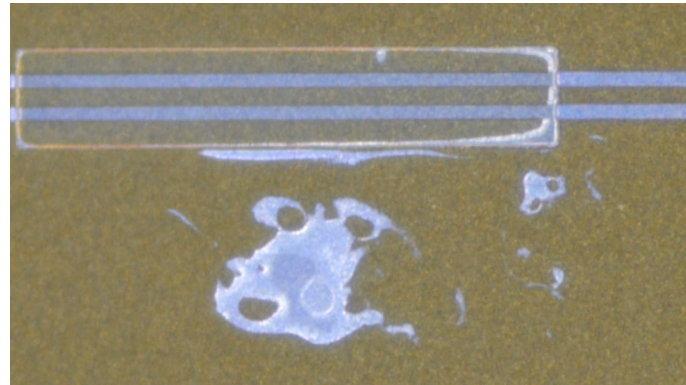
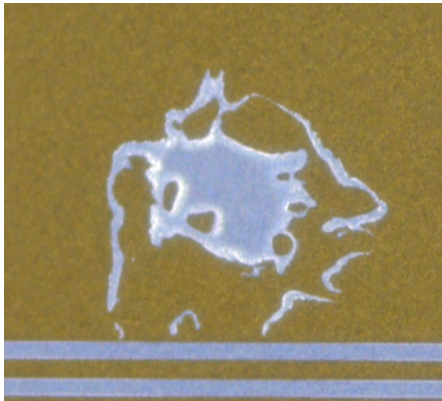
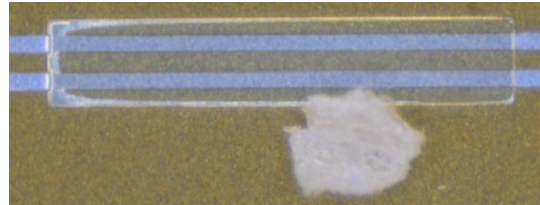
# Self build teststructures

- 5cm to 20cm long test structures produced and bonded to pcb
- Dimensions 40um/40um/3um width/gap/height
- Currently fully aluminum, planned to increase thickness to 6 um and to investigate copper process
- measurements of resistance, TDR and eyediagrams
- Future plans to test transmission properties with FPGA



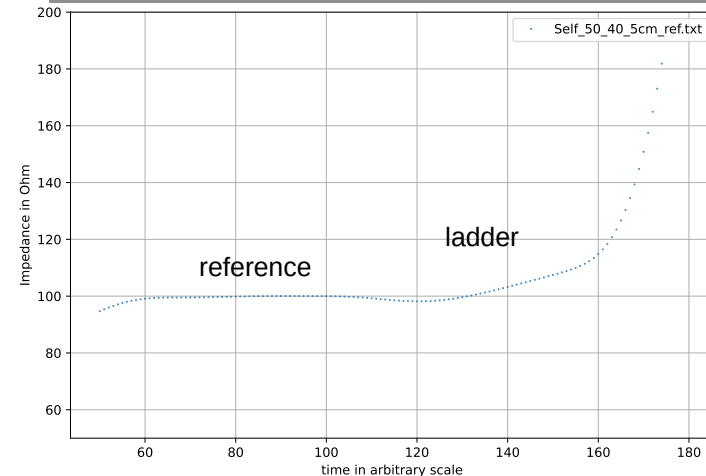
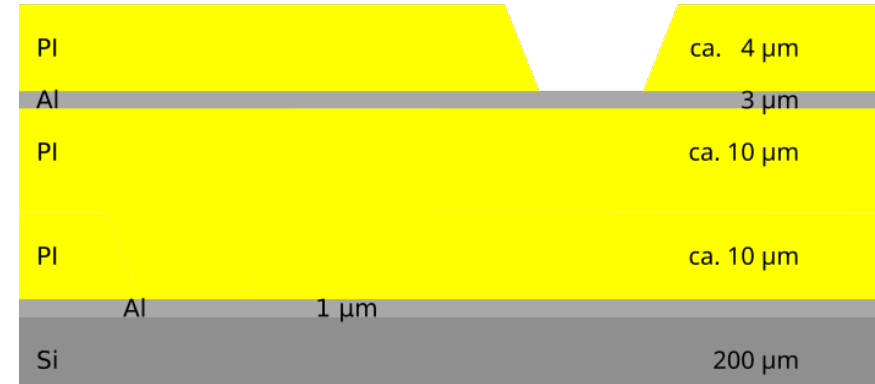
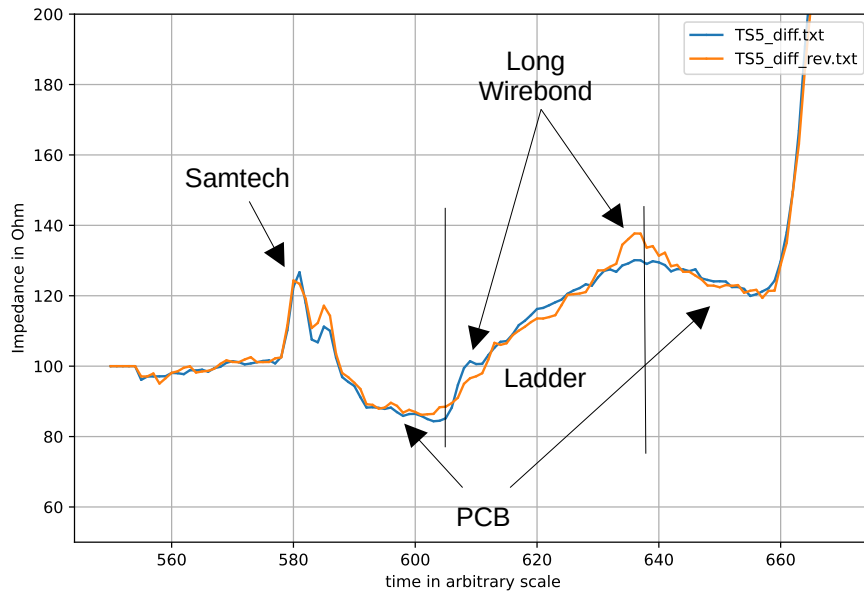
## Some defects (process need refinement)

- Some defects found on the new structures:



# Layer Stack-up Teststructures FTD

- width/gap: 50/40
- Simulation:  $Z_0 = 98.5\Omega$



## Conclusion

- Talking to IZM for new test structures and first Obelix prototypes
  - Two approaches, ladder first preferred
- Impedance measurement agrees well with simulations (simulation of complete design ongoing)
- Eye diagrams show wide open eyes
- Flex cable design soon to be finished
  - Looking for manufacturer, then order and test
- Bending issues quickly investigated, will follow with thinned modules
- New RDL design will be started soon

